

L Number	Hits	Search Text	DB	Time stamp
1	626	("low k" or "methyl doped silica" or "fluorinated silicon glass" or FSG) and (PECVD or "plasma enhanced chemical vapor deposition")	USPAT; EPO; JPO; IBM_TDB	2003/06/02 15:12
2	86	(("low k" or "methyl doped silica" or "fluorinated silicon glass" or FSG) and (PECVD or "plasma enhanced chemical vapor deposition")) and power and ("methyl silane" or ("nitrous oxide" or "NO.sub.2"))	USPAT; EPO; JPO; IBM_TDB	2003/06/02 13:38
3	1		USPAT	2003/06/02 13:21
6	107	(("low k" or "methyl doped silica" or "fluorinated silicon glass" or FSG) and (PECVD or "plasma enhanced chemical vapor deposition")) and ("methyl silane" or ("nitrous oxide" or "NO.sub.2"))	USPAT; EPO; JPO; IBM_TDB	2003/06/02 15:12
7	391	("low k" or "methyl doped silica" or "fluorinated silicon glass" or FSG) and (PECVD or "plasma enhanced chemical vapor deposition") and power	USPAT; EPO; JPO; IBM_TDB	2003/06/02 13:52
12	89	(("black diamond" or "methyl doped silica" or "low k") and (PECVD or "plasma enhanced chemical vapor deposition")) and ("methyl silane" or ("nitrous oxide" or "NO.sub.2"))	USPAT; EPO; JPO; IBM_TDB	2003/06/02 15:05
13	37	(("black diamond" or "methyl doped silica" or "low k") and (PECVD or "plasma enhanced chemical vapor deposition")) and "methyl silane"	USPAT; EPO; JPO; IBM_TDB	2003/06/02 15:06
11	506	("black diamond" or "methyl doped silica" or "low k") and (PECVD or "plasma enhanced chemical vapor deposition") "low k" and "methyl silane" and ("nitrous oxide" or "NO.sub.2") and (helium or He) and (oxygen or "O.sub.2") and power	USPAT; EPO; JPO; IBM_TDB	2003/06/02 16:08
14	20		USPAT; EPO; JPO; IBM_TDB	2003/06/02 15:14
15	1		USPAT	2003/06/02 16:04
16	28	"black diamond" and (PECVD or "plasma enhanced chemical vapor deposition")	USPAT; EPO; JPO; IBM_TDB	2003/06/02 16:23
17	65	("black diamond" or "methyl doped silica") and (CVD or "chemical vapor deposition")	USPAT; EPO; JPO; IBM_TDB	2003/06/02 16:24